

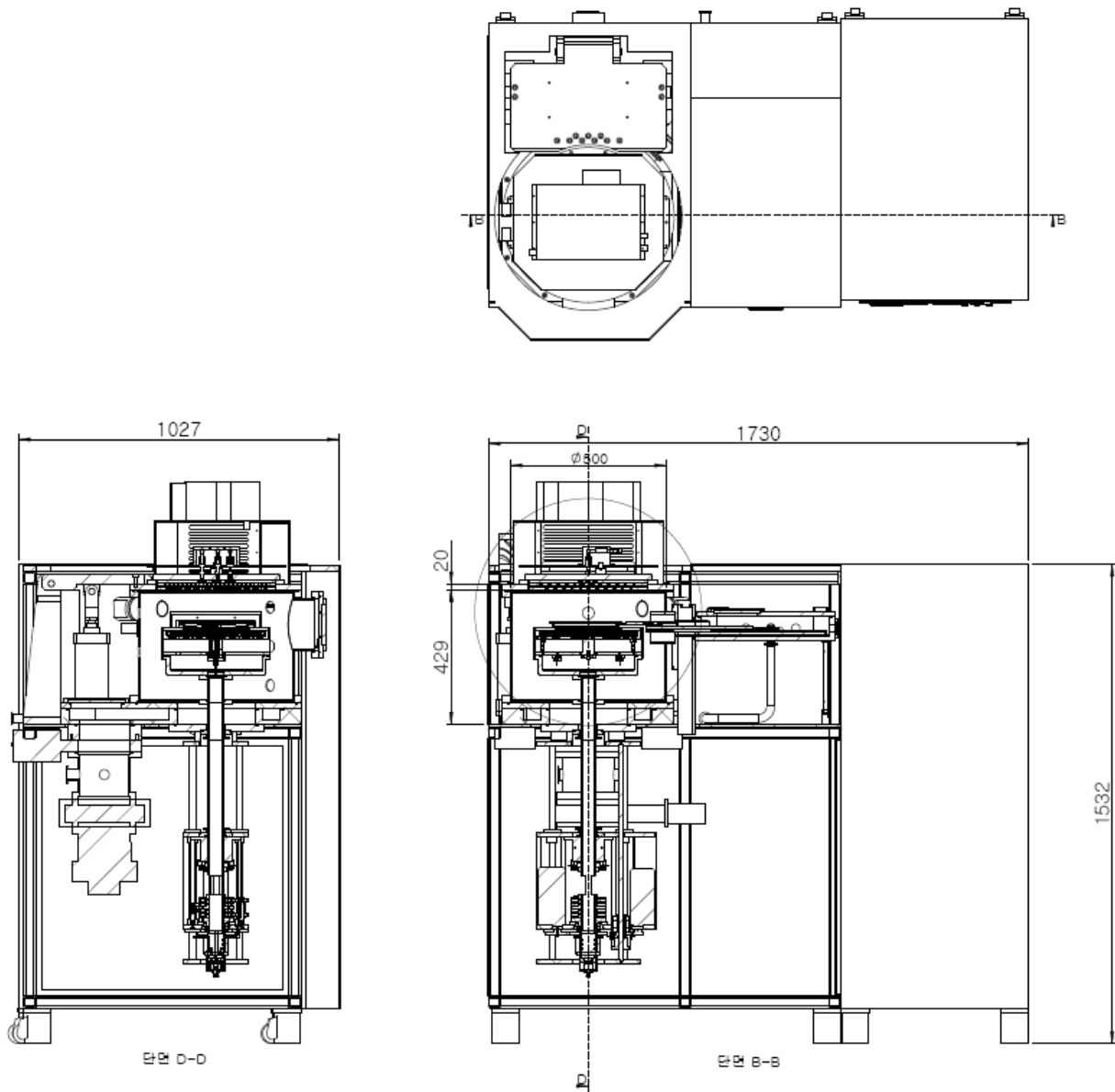
ATS-CVD Series PECVD System for Solar Cell AR Coatings



Special Features

- ◆ Capacitively-Coupled PECVD system with loadlock chamber for R&D and small scale production
- ◆ Automatic loadlock system with cassette
- ◆ Uniform gas distribution through shower head
- ◆ Substrate temperature uniformity : $\leq \pm 2^\circ\text{C}$ @400°C within 6"
- ◆ Thickness uniformity of deposited layers : $< \pm 2\%$ @100nm within 6" (5mm edge exclusion)
- ◆ Applications
 - SiNx dielectric material coatings
 - SiOx dielectric material coatings
- ◆ Wafer capacity
 - 1 × 6"
- ◆ Cycle time: <15mins
- ◆ Average throughput
 - Up to 26,200 wafers per year
- ◆ Dimension
 - 1,730L × 1,027H × 1,832W (mm³)
- ◆ Others
 - Power : AC 2kW (13.56MHz)
 - VHF & MF Power compatible
 - Gas : NF₃/O₂/H₂/SiH₄/N₂/NH₃/N₂O/Ar
 - Substrate material : Si
 - Pump : Dry(1,200l/min & 200l/min)
 - turbo(600l/s)

◇ Layout



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